



Reg. No. : .....

Name : .....

Third Semester B.Tech. Degree Examination, November 2013  
(2008 Scheme)  
08.302 : SOLID STATE DEVICES (TA)

Time : 3 Hours

Max. Marks : 100

PART – A

Answer **all** questions. **Each** question carries **4** marks.

1. Derive the continuity equation for holes and electrons in a semi conductor.
2. With neat diagram explain the Fermi-Dirac distribution applied to semi conductors.
3. A GaAs sample is doped so that the electron-hole components of currents are equal in an applied electric field. Calculate the equilibrium electron-hole concentrations, the net doping and the sample resistivity at 300 K  
 $\mu_n = 8500 \text{ cm}^2 / \text{Vs}$   $\mu_p = 400 \text{ cm}^2 / \text{Vs}$   $n_i = 1.79 \times 10^6 \text{ cm}^{-3}$ .
4. With neat diagram distinguish between direct and indirect band semiconductor.
5. Derive the junction capacitance of a linearly graded junction.
6. Explain with neat diagram Avalanche Breakdown.
7. An n channel Si JFET has  $N_d = 10^{16} \text{ cm}^{-3}$   $N_a = 10^{19} \text{ cm}^{-3}$  and  $a = 1 \text{ } \mu\text{m}$ . Determine the
  - a) built in voltage
  - b) pinch off voltage.
8. What is a punched through diode ? What are its advantage ?
9. Explain the C-V characteristics of ideal MOS system.
10. Explain the principle of operation of JFET.





## PART – B

Answer **any two** questions from **each** Module. **Each** question carries **10** marks.

## Module – I

11. State and derive Einstein's relation.
12. Explain Hall effect. Explain the procedure to measure majority carrier concentration and mobility of a semi conductor specimen.
13. Intrinsic Ge sample at room temperature has resistivity of  $50 \Omega \text{ cm}$ . The sample is doped to the extent of  $6 \times 10^{13}$  As atoms/cm<sup>3</sup> and  $10^{14}$  Boron atoms per cm<sup>3</sup>. Find the conduction current density if an electric field of  $4 \text{ V/cm}$  is applied across the sample  $\mu_n = 3800 \text{ cm}^2 / \text{Vs}$   $\mu_p = 1800 \text{ cm}^2 / \text{Vs}$ .

## Module – II

14. Derive expressions for injection efficiency transport factor,  $\alpha$  and  $\beta$  of a p-n-p transistor operating in the active region in terms of the doping and dimensions of the different regions of the transistor.
15. Define the figure of merit of a BJT. Derive the expression for the same.
16. a) Explain the principle of operation of Schottky diode and derive the current equation.  
 b) An ideal Silicon abrupt p-n junction has  $N_A = 10^{16}$ ,  $N_D = 10^{14} \text{ Cm}^{-3}$ .  $\tau_n = \tau_p = 0.1 \mu\text{s}$   $A = 10^{-3} \text{ cm}^2$ ,  $D_p = 10 \text{ cm}^2/\text{s}$ .  $D_n = 24 \text{ cm}^2/\text{s}$ . Determine the dynamic forward resistance of the diode at  $300 \text{ K}$  with forward voltages of  
 a)  $0.5 \text{ v}$                       b)  $0.6 \text{ V}$ .

## Module – III

17. Explain the principle of operation of an SCR.
  18. a) An n channel Si JFET has  $N_A = 10^{19} \text{ cm}^{-3}$   $N_D = 10^{15} \text{ cm}^{-3}$  and  $a = 4 \mu\text{m}$ . Determine at  $300 \text{ K}$   
 a) pinch-off voltage  
 b) the gate bias required to make the thickness of the undepleted channel equal to  $1 \mu\text{m}$  with  $V_{DS} = 0$ .  
 b) Define the threshold voltage of ideal MOS capacitor.
  19. Explain the structure and principle of operation of depletion mode MOSFET. Derive expression for drain current.
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